ABSTRACT

In the manufacture of a semiconductor device, an arrangement for forming a layer on a semiconductor substrate compensates for variations in wafer substrate reflectivity.

The arrangement includes providing substrate illumination and then adjusting the illumination on the substrate. The arrangement also includes controlling the dispensation of material over the substrate as a function of the adjusted illumination. By compensating for variations in wafer substrate reflectivity, manufacturing processes can realize more consistent photoresist coatings on wafer substrates from one wafer lot to another.